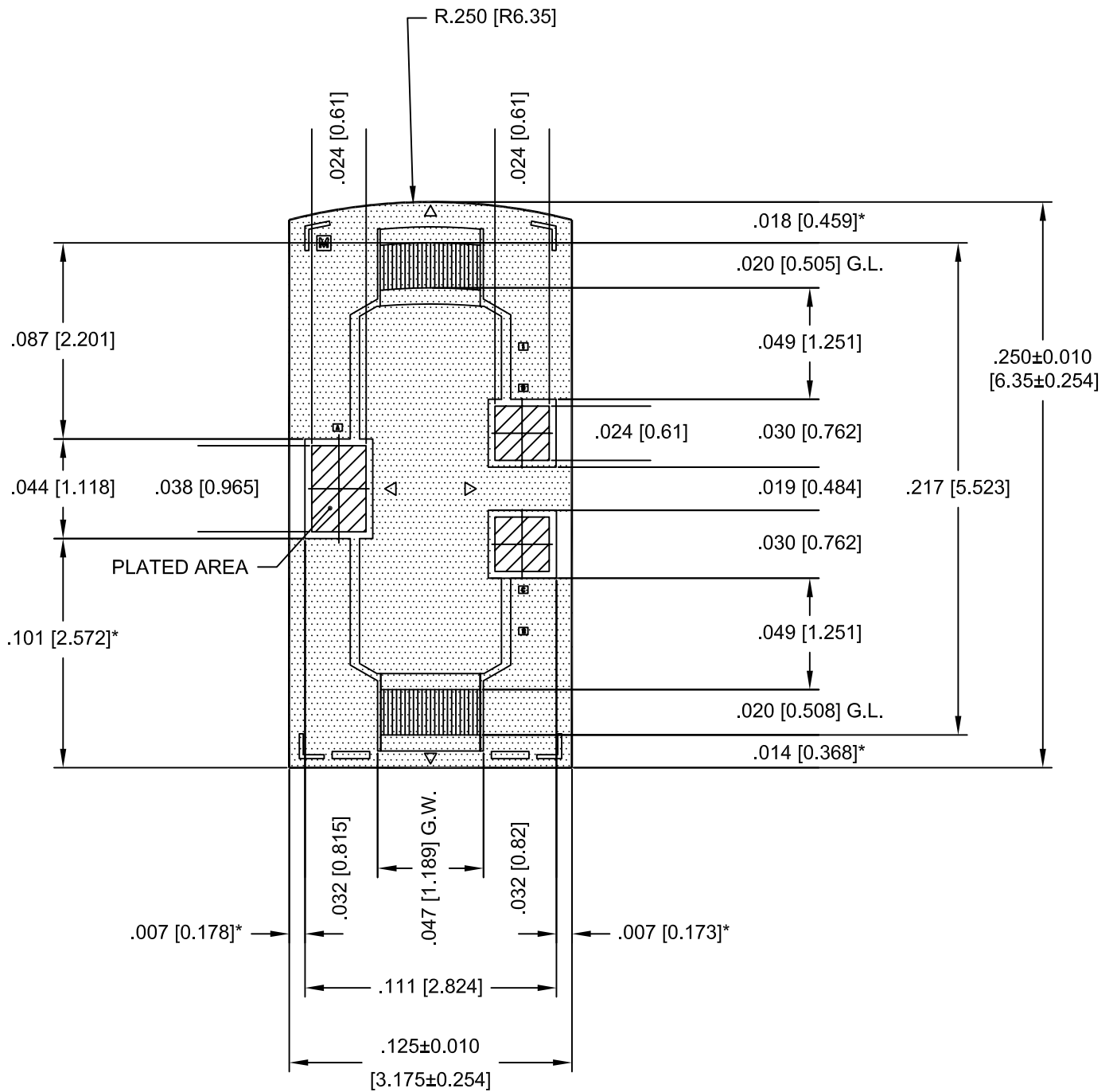


LTR	REVISION	ERN	INITIAL	DATE
A			AR	2012-05-10



\* THESE MATRIX RELATED DIMENSIONS ARE ±0.005

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Micro-Measurements  
Raleigh, North Carolina USA



S5050  
HALF DIAPHRAGM  
PATTERN LAYOUT

CONSTRUCTION:

N5K

OPTIONS:

DG, E3, N2

RESISTANCE:

3000±0.3%

REFERENCE:

DRAWN BY:

AR

PROJ. ENG.

GY

DATE:

2012-05-10

DATE:

2012-05-10

SCALE:

N.T.S.

DWG. #

MS-S5050-10031

ALL DIMENSIONS ARE IN INCHES UNLESS OTHERWISE SPECIFIED.

REVISION:

A